

4. (Amended) Method as according to claim 1, characterized in that detected differences between the measured value and the target value are taken into consideration by means of adding an offset to any desired target value for a further modification procedure.

5. (Amended) Method as according to claim 1, characterized in that the offset is calculated as the absolute or relative difference between the first target value and the corresponding obtained value as measured.

6. (Amended) Method as according to claim 1, characterized in that the offset is a function of an averaged and filtered measured voltage ($\langle U_{\text{actual}} \rangle$) of piezoelectric elements (10, 20, 30, 40, 50, 60) and an averaged and filtered target voltage ($\langle U_{\text{target}} \rangle, \langle U_{\text{offset,p}} \rangle$) for said piezoelectric elements (10, 20, 30, 40, 50, 60).

7. (Amended) Method as according to claim 1, characterized in that the averaged and filtered target voltage ($\langle U_{\text{target}} \rangle, \langle U_{\text{offset,p}} \rangle$) of piezoelectric elements (10, 20, 30, 40, 50, 60) is a function of an averaged and filtered voltage offset value ($\langle U_{\text{offset,p}} \rangle$) and an averaged and filtered initial target voltage ($\langle U_{\text{target}} \rangle$) for the piezoelectric elements (10, 20, 30, 40, 50, 60).

8. (Amended) Method as according to claim 1, characterized in that an offset is determined for each of top-closed position, up-open position and down-open position of the piezoelectric elements (10, 20, 30, 40, 50 and 60).

9. (Amended) Method as according to claim 1, characterized in that an offset is stored as long as a corresponding position of the piezoelectric elements (10, 20, 30, 40, 50 and 60) is not used.

10. (Amended) Apparatus, characterized in that

a. modification means (A, E, D) for the modification of system parameters according to at least one control parameter;

b. measuring means (E, D; 600, 610) for the measurement of the value of the

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- resulting system parameter;
- c. comparison means (E, D) for the comparison of the measured value to a predefined target value; and
 - d. calculation means (D) for the calculation of at least one control parameter for a further modification of the system parameter in accordance with differences occurring between the measured value and the target value are implemented within the apparatus.

REMARKS

Attached hereto is a marked-up version of the changes made to the claims by the current amendment. The attached page is captioned "VERSION WITH MARKINGS TO SHOW CHANGES MADE."

Respectfully submitted,

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By:

By: *Richard L. Mayer*
B No 35,952

Richard L. Mayer

Reg. No. 22,490

KENYON & KENYON